

ATI-0016

IN THE SPECIFICATION

Kindly correct typographical error in paragraph [0020], the third sentence as follows:

[0020] As previously disclosed, the photons could be included in ultraviolet (UV), x-ray, and/or other forms of electromagnetic radiation. For exemplary purposes, reference will now be made in detail to the preferred embodiments, wherein the photon source is a UV light source. The use of other ~~proten~~photon sources will be well within the skill of those in the art in view of this disclosure.

Kindly correct typographical error in paragraph [0031], the second sentence as follows:

[0031] The drying process includes loading the substrate 18 into the process chamber 12 and exposing the substrate 18 to UV radiation emitted by the radiation source 20. Preferably, the process chamber ~~112-12~~ is configured for automatic handling such that manual handling of the substrate 18 is eliminated. In a preferred embodiment, the process includes purging the process chamber 12 with one or more inert gases to remove the air within the process chamber 12 and then exposing the substrate 18 to UV radiation. Suitable inert gases for purging air from the process chamber 12 include, but are not limited to, nitrogen, argon, helium, forming gas, combinations comprising at least one of the foregoing gases, and the like. Simultaneous with or subsequent to the UV radiation exposure, the substrate may be subjected to heat and/or a vacuum for removing the volatile components from the low k dielectric layer.

Kindly correct typographical error in paragraph [0034], the first sentence as follows:

[0034] Referring now to Figure ~~42~~, an FTIR was obtained of the substrate before and after the UV drying process. The results clearly show that moisture is removed from the low k dielectric surface as demonstrated by the absence of peaks at about 3000 to about 3400 and about 1400 cm^{-1} .